

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicants: Ogata et al.

Examiner: Lee, Sin J

Application No.: 10/589,382

Group Art Unit: 1795

Filed: August 15, 2006

Docket: 1608-6 PCT/US

For: **PHOTORESIST COMPOSITION
AND METHOD OF FORMING RESIST
PATTERN**

Dated: January 26, 2009

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DO NOT ENTER: /SL/

Dated: January 26, 2009

Signature: K.J. Goodhand 

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

RESPONSE TO OFFICE ACTION UNDER 37 C.F.R. §1.111

Sir:

In response to the final Office Action dated October 30, 2008, the due date for which is January 30, 2009, please amend the above-identified application as follows:

Amendments to the Claims are reflected in the listing of claims which begins on page 2 of this paper.

Remarks begin on page 5 of this paper.

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